Tungsten growth on silicon dioxide and boron carbide and additional role of spacer in the ultrashort period multilayer X-ray mirrors

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Grazing-incidence small-angle X-ray scattering (GISAXS)





$$\vec{k} = \vec{k}_f - \vec{k}_i \text{ scattering vector}$$

$$k_x = 2\pi / \lambda(\cos\alpha_f \cos 2\theta_f - \cos\alpha_i)$$

$$k_y = 2\pi / \lambda\cos\alpha_f \sin 2\theta_f$$

$$k_z = 2\pi / \lambda(\sin\alpha_f + \sin\alpha_i)$$

Coplanar versus non-coplanar geometry







Co/C mirror for water window (d = 2.3nm, N = 200) cross-sectional TEM reveals granular multilayer

GISAXS – fast probe of interface quality



RF sputtering



Mo/Si mirrors for EUV lithography

Grazing-incidence small-angle X-ray scattering (GISAXS)

$$\begin{aligned} & \operatorname{CuK}_{\alpha} \qquad \alpha_{i} = \alpha_{f} = 0.7^{\circ} \qquad 2\theta_{f} = 1^{\circ} \\ & k_{x} \stackrel{\wedge}{=} -0.006 \ nm^{-1} \rightarrow \Lambda_{x} \stackrel{\wedge}{=} 1011 \ nm \\ & k_{y} \stackrel{\wedge}{=} 0.7 \ nm^{-1} \qquad \rightarrow \Lambda_{y} \stackrel{\wedge}{=} 8.8 \ nm \\ & k_{z} \stackrel{\wedge}{=} 1 \ nm^{-1} \qquad \rightarrow \Lambda_{z} \stackrel{\wedge}{=} 6.3 \ nm \end{aligned}$$

- ✤ nanometer-scale in-plane and in-depth resolutions are easily accessible
- * lateral k_y and vertical k_z components of the scattering vector are independent of each other => simple BA theory is fully sufficient
- ✤ simple experimental arrangement
- intuitive shape of GISAXS pattern => modelling is not always necessary

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- ✤ GISAXS patterns provides FT of 2D autocorrelation function of the probed surface



Dual ion-beam sputtering system



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- * 30 W microfocus X-ray source IµS (Incoatec), Cu K_{α} radiation
- X-ray detector Pilatus 200K (Dectris)
- total X-ray flux 1×10⁸ ph/s

Multilayer mirror growth by in-situ GISAXS



W/B₄C mirror, 1.5 nm period, N=15 (d_W =0.6 nm, d_{B4C} =0.9 nm) α_i = 0.25^o deposition time \approx 54 min.

Self-affine versus mounded surfaces





- $\operatorname{PSD}(k) = \frac{w^2 \xi^2}{4\pi} \exp\left[-\frac{\left(4\pi^2 + k^2 \lambda^2\right) \xi^2}{4\lambda^2}\right] J_0\left(\frac{\pi k \xi^2}{\lambda}\right)$
 - w interface width (surface rms roughness)
 - $\xi~$ lateral correlation length
 - λ mound period (inter-cluster distance)
 - J_0 Bessel function of zero order

Self-affine versus mounded surfaces



2D layer-by-layer growth





3D cluster growth

From self-affine to mounded surface



slope < 0 => 2D growth slope > 0 => 3D growth

From self-affine to mounded surface



ultra-short period multilayer slope < 0

Power spectral density from GISAXS





Lateral cut of GISAXS pattern at the exit angle close to the critical value for total reflection of the substrate is proportional to PSD function of the growing surface.

Power spectral density from GISAXS





Lateral cut of GISAXS pattern at the exit angle close to the critical value for total reflection of the substrate is proportional to PSD function of the growing surface.

Temporal evolution of lateral cuts of GISAXS patterns



Temporal evolution of PSD slope derived from GISAXS



TEM, XRR



W/B₄C multilayer on Si/SiO₂ substrate, d = 1.5 nm, N = 300, Γ = 0.33, $\alpha_{\rm i}$ = 0.25^o

3D growth of tungsten on SiO₂



3D growth of tungsten on SiO₂



Message

- Buildup of interfaces in W/B₄C mirrors is governed by an interplay between W agglomeration on SiO₂ and counteracting 2D layer-by-layer growth favored by B₄C.
- "Healing" effect of B₄C on the interface roughness plays a crucial role in the preparation of ultrashort-period multilayer mirrors without a need for additional interface treatment.
- In-situ GISAXS analysis revealed an additional role of the spacer beyond a merely optical one.
- Potential of laboratory-based in-situ GISAXS for analyses of multilayer growth was demonstrated using the latest-generation microfocus X-ray sources and fast 2D detectors.

Co-workers



Projects

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Thank you for your attention !

